

Introducing the IKONIC™ 2000 CMP Polishing Pad Series

The IKONIC™ 2000 series of polishing pads targets copper barrier polishing and other processes that require soft and ultra-soft pads. Although soft, these pads are formulated for easier conditioning to maintain proper texture. The 2000 series is designed to deliver a step-out improvement in wafer defect levels, consistent and stable removal rates, and longer pad lifetime. IKONIC™ 2000 polishing pads are available for sampling today.

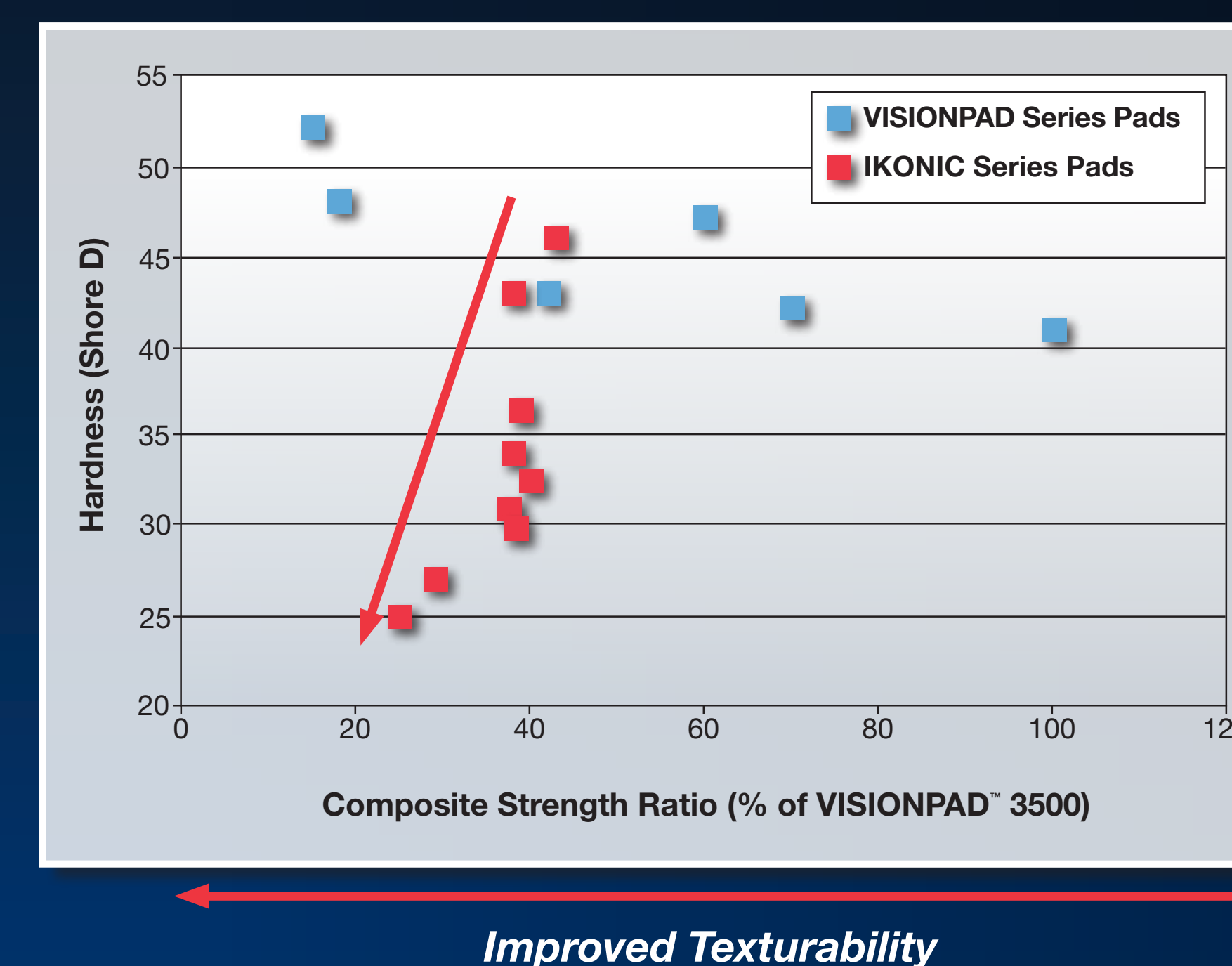
Features:

- New, unique chemistry
- Multiple product offerings
- A range of hardness and porosity
- Advanced groove configurations
- Pads for Copper Barrier, Buffing and HKMG

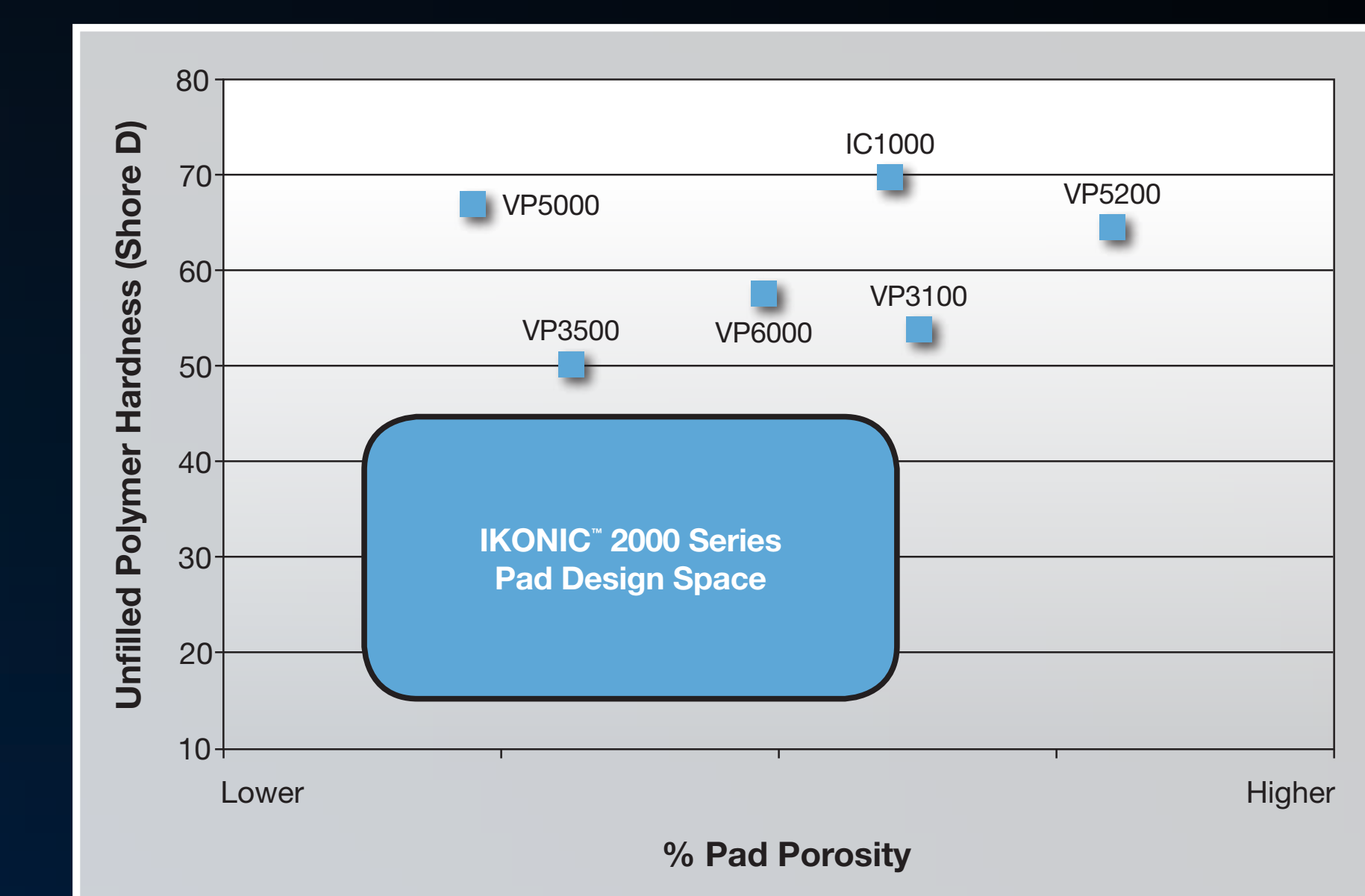
Benefits:

- Step-out defectivity performance
- Multiple offerings to meet a range of removal rate and selectivity requirements
- Extended pad lifetime
- Easily conditioned pad surface

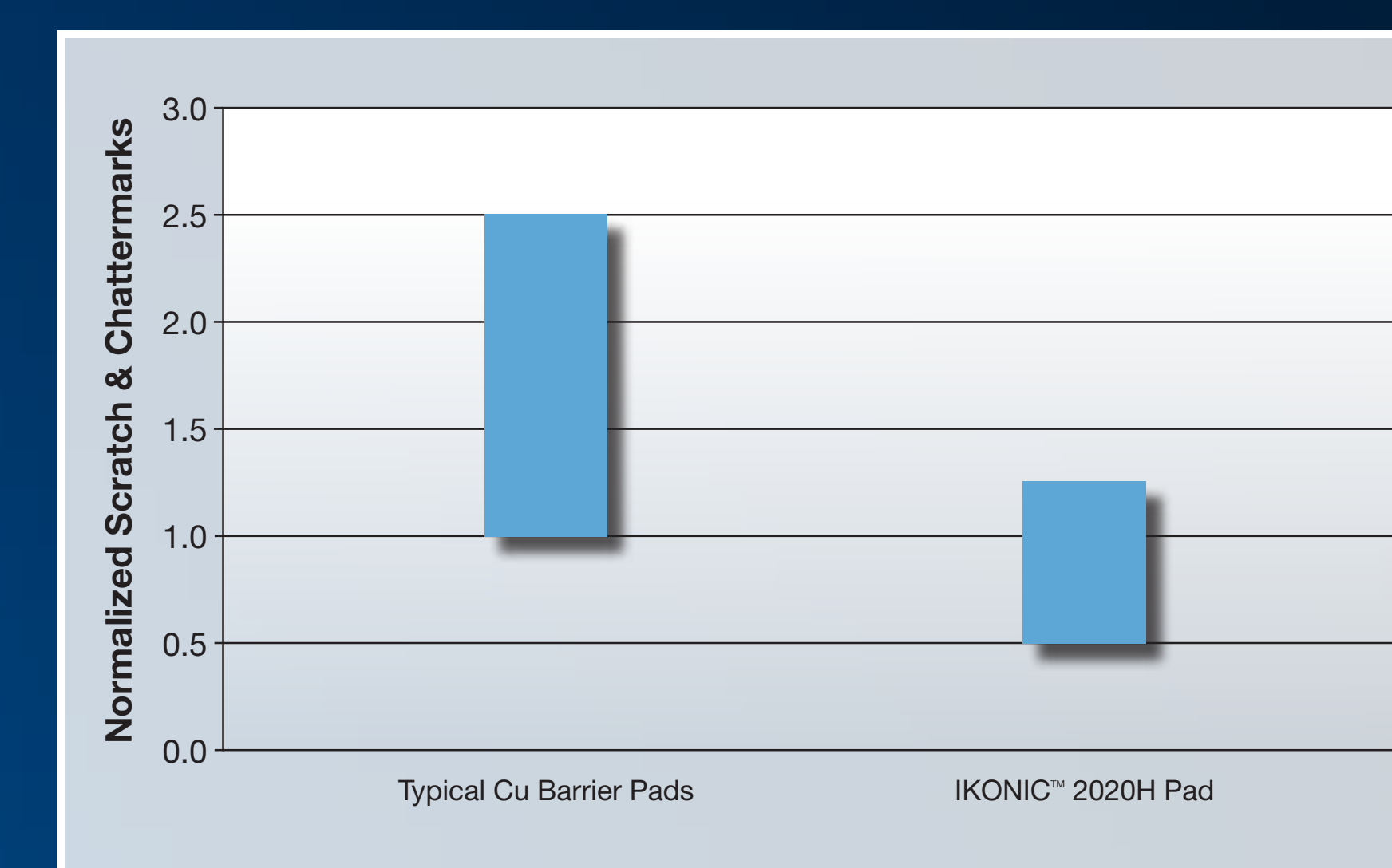
Low hardness pads with reduced composite strength for easier conditioning



A range of hardness and porosity to satisfy multiple process needs



IKONIC™ 2020H demonstrates low defect levels in copper barrier polishing





Introducing the IKONIC™ 3000 CMP Polishing Pad Series

The IKONIC™ 3000 series of polishing pads targets copper bulk polishing and other processes that require medium-hardness pads. The 3000 series is designed to deliver a step-out improvement in wafer defect levels and improved topography performance when compared to IC1000™ and VISIONPAD™ 6000. IKONIC™ 3000 polishing pads are available for sampling today.

Features:

- New, unique chemistry
- Advanced groove configurations
- Window options for end point detection
- Available in large diameter sizes
- Pads for Copper Bulk and processes requiring medium hardness pads

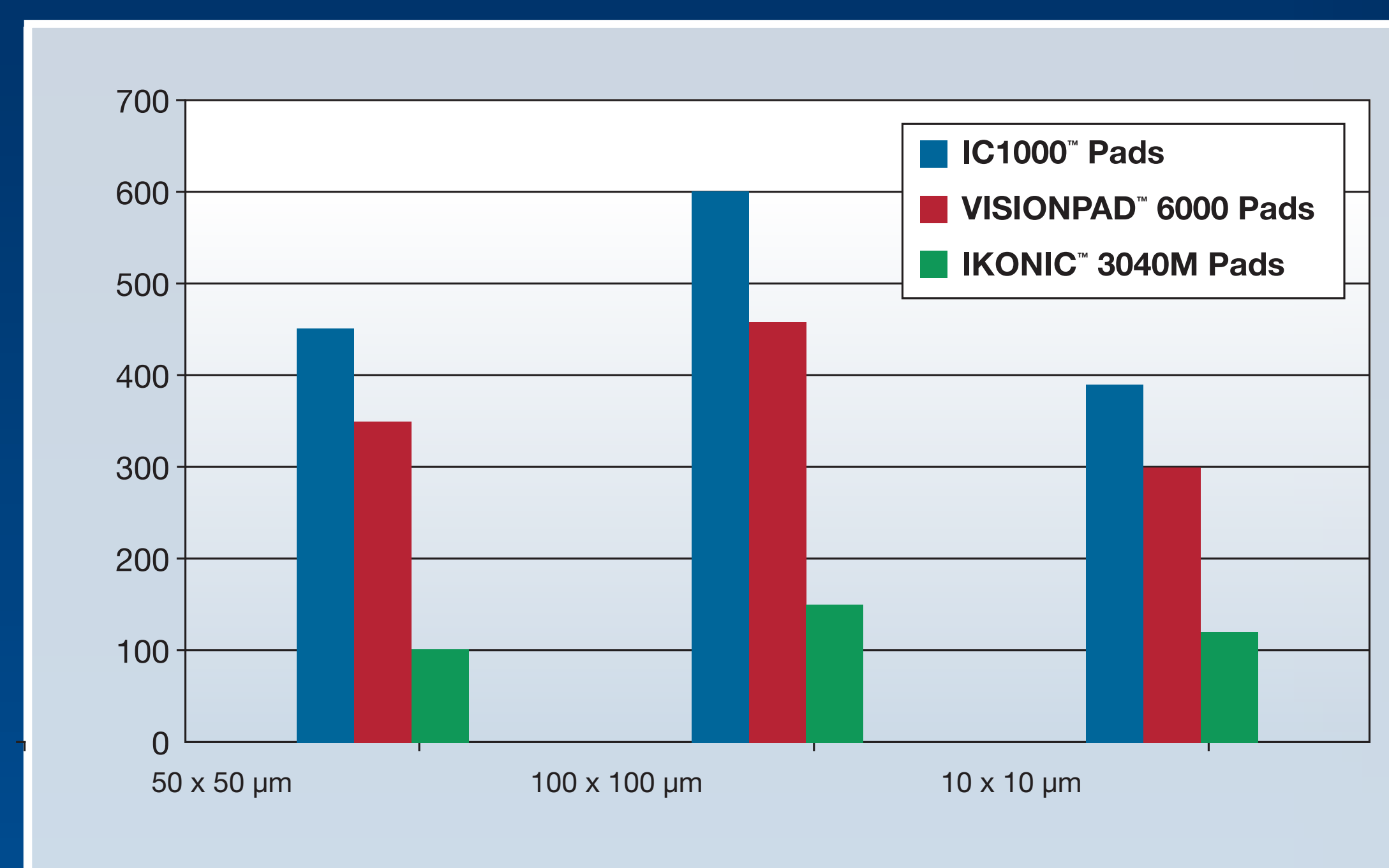
Benefits:

- Improved defectivity performance
- Improved topography performance
- Multiple configuration options
- Extended pad lifetime
- Easily conditioned pad surface

Comparison of IC1000™, VISIONPAD™ 6000 and IKONIC™ 3040M

Product	S.G. g/cm ³	Shore D Hardness
IC1000™ Polishing Pad	0.80	60
VISIONPAD™ 6000 Polishing Pad	0.81	53
IKONIC™ 3040M Polishing Pad	0.88	46

IKONIC™ 3040M demonstrates improved topography performance



IKONIC™ 3040M demonstrates low defect levels compared to IC1000™ and VP6000™

